

Message Text

CONFIDENTIAL

PAGE 01 STATE 171900

70

ORIGIN EB-07

INFO OCT-01 CIAE-00 COME-00 DODE-00 NRC-05 NSAE-00 USIA-06

TRSE-00 EUR-12 ERDA-05 ISO-00 ACDA-07 MC-02 /045 R

DRAFTED BY EB/ITP/EWT:LROSS

APPROVED BY EB/ITP/EWT:RWPRACHT

COMMERCE/OEA:MHUTCHINSON

RPE

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P 122015Z JUL 76

FM SECSTATE WASHDC

TO USMISSION OECD PARIS PRIORITY

CONFIDENTIAL STATE 171900

EXCON

E.O. 11652: XGDS-1

TAGS: ESTC, COCOM, CZ, GW

SUBJECT: GERMAN MASK ALIGNMENT AND EXPOSURE SYSTEM TO
CZECHOSLOVAKIA - IL 1355

REFS: A) OECD PARIS 19439, B) OECD PARIS 18776,

C) COCOM DOC (76)1022, D) COCOM DOC (75)2307

CONTINUE RESERVE. REQUEST CLARIFICATION OF NEED FOR SIMUL-
TANEOUS EXPOSURE OF BOTH SIDES OF WAFER BEING PROCESSED.
US TECHNICIANS DO NOT UNDERSTAND STATEMENT IN FIRST SENTENCE
OF PARA 5 REF C. KISSINGER

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NNN

Message Attributes

Automatic Decaptoning: X
Capture Date: 01 JAN 1994
Channel Indicators: n/a
Current Classification: UNCLASSIFIED
Concepts: EQUIPMENT, STRATEGIC TRADE CONTROLS, EXCEPTIONS LIST
Control Number: n/a
Copy: SINGLE
Draft Date: 12 JUL 1976
Decaption Date: 01 JAN 1960
Decaption Note:
Disposition Action: RELEASED
Disposition Approved on Date:
Disposition Authority: KelleyW0
Disposition Case Number: n/a
Disposition Comment: 25 YEAR REVIEW
Disposition Date: 28 MAY 2004
Disposition Event:
Disposition History: n/a
Disposition Reason:
Disposition Remarks:
Document Number: 1976STATE171900
Document Source: CORE
Document Unique ID: 00
Drafter: LROSS
Enclosure: n/a
Executive Order: X1
Errors: N/A
Film Number: D760268-0475
From: STATE
Handling Restrictions: n/a
Image Path:
ISecure: 1
Legacy Key: link1976/newtext/t19760767/aaaacgxi.tel
Line Count: 47
Locator: TEXT ON-LINE, ON MICROFILM
Office: ORIGIN EB
Original Classification: CONFIDENTIAL
Original Handling Restrictions: n/a
Original Previous Classification: n/a
Original Previous Handling Restrictions: n/a
Page Count: 1
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Previous Classification: CONFIDENTIAL
Previous Handling Restrictions: n/a
Reference: 76 OECD PARIS 19439, 76 OECD PARIS 18776
Review Action: RELEASED, APPROVED
Review Authority: KelleyW0
Review Comment: n/a
Review Content Flags:
Review Date: 20 APR 2004
Review Event:
Review Exemptions: n/a
Review History: RELEASED <20 APR 2004 by CunninFX>; APPROVED <13 SEP 2004 by KelleyW0>
Review Markings:

Margaret P. Grafeld
Declassified/Released
US Department of State
EO Systematic Review
04 MAY 2006

Review Media Identifier:
Review Referrals: n/a
Review Release Date: n/a
Review Release Event: n/a
Review Transfer Date:
Review Withdrawn Fields: n/a
Secure: OPEN
Status: NATIVE
Subject: GERMAN MASK ALIGNMENT AND EXPOSURE SYSTEM TO CZECHOSLOVAKIA - IL 1355
TAGS: ESTC, CZ, GE, COCOM
To: OECD PARIS
Type: TE
Markings: Margaret P. Grafeld Declassified/Released US Department of State EO Systematic Review 04 MAY 2006